

Patent Application
10/010,162

REMARKS

Claims 12-22 are pending in the application. Claims 12 and 22 are the only independent claims, and each has been amended herein.

Objection to the drawings

Paragraph 1 of the final Action indicates that the drawings received on 10/13/03 "are not acceptable" "because the lines and numbers defining the drawings are blurred and not clearly legible".

Formal drawings are submitted herewith. Withdrawal of the objection to the drawings is respectfully requested.

Section 102 and 103 rejections

Claims 12-20 and 22 were rejected under 35 USC 102(c) as being anticipated by US Patent 6,211,018 B1 (Nam et al.) and Claims 21 was rejected under 35 USC 103(a) as being unpatentable over Nam.

In view of the following discussion, each of the rejections is respectfully traversed and reconsideration is requested.

Each of the independent claims, Claims 12 and 22, has been amended herein to recite a method of forming a trench MOSFET including the step of providing a patterned first masking material layer over an epitaxial layer, the *patterned first masking material layer comprising a densified non-doped silica glass layer overlaid by a positive photoresist material*, and the patterned first masking material layer comprising a first aperture, and the step of depositing a second masking material layer over the first masking material layer, the second masking material layer comprising a densified non-doped silica glass layer.

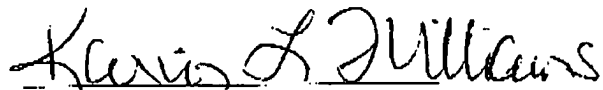
This limitation is supported by the application as filed, at least in paragraph [0025] found at page 6 of the specification.

Nam fails to teach or suggest a method in accordance with each of amended independent Claims 12 and 22. For at least the foregoing reason, Applicants respectfully submit that each of independent Claims 12 and 22 is patentable over Nam and reconsideration is requested.

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Dependent Claims 13-21 are believed to be clearly patentable for all of the reasons indicated above with respect to Claim 12, from which they depend, and even further distinguish over Nam by reciting additional limitations. Should the Examiner be of the view that an interview would expedite consideration of the application, request is made that the Examiner telephone the Applicants' attorney at (908) 518-7700 in order that any outstanding issues be resolved.

Respectfully submitted,



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